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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Jung-ho LEE, et al.

Art Unit: 2818

Serial No. 10/779,733

Examiner: Renee R. Berry

Filed: February 18, 2004

*Confirmation No. 2084*

For: METHOD OF FORMING SILICON OXIDE LAYER  
IN SEMICONDUCTOR MANUFACTURING  
PROCESS

Attorney Docket No. 253/006 CIP 2

**REPLY UNDER 37 C.F.R. §1.111**

Mail Stop Amendments  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Va. 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

In response to the Office action mailed June 13, 2005, please consider the following remarks:

**A Listing of the Claims** begins on page 2 of this paper.

**Remarks/Arguments** begin on page 7 of this paper.